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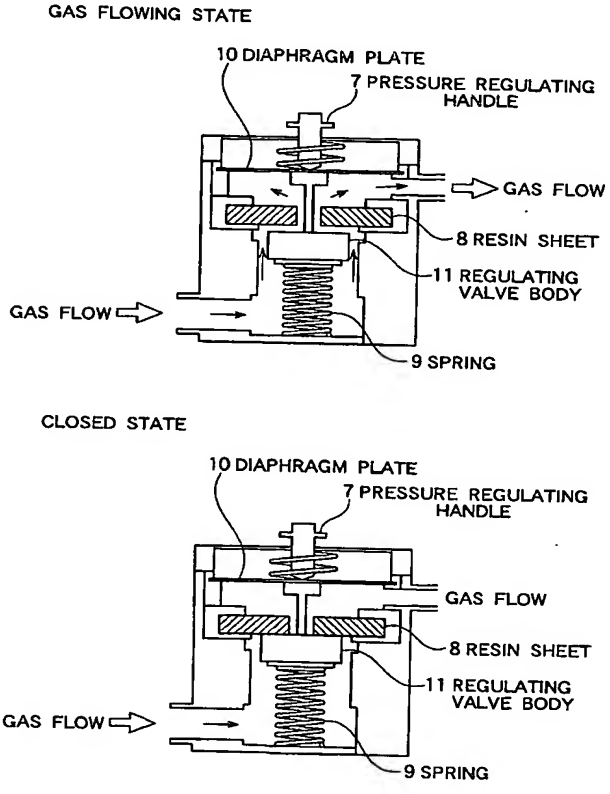
(54) Title: APPARATUS AND METHOD FOR FEEDING HIGH-PURITY AMMONIA GAS



(57) Abstract: It is an object of the present invention to provide a system for feeding a high-purity ammonia gas, where a feeding apparatus free from generation of a particle due to corrosion and not causing the formation of a corrosion or reaction product inside the gas feeding path, such as cylinder valve, pressure regulator, pressure gauge, mass flow controller, line valve and filter, is appropriately employed for the gas flow path from a gas cylinder to a production apparatus, thereby realizing more safe and highly efficient feeding of the high-purity ammonia gas without deteriorating the purity and production of a semiconductor device having higher performance. The apparatus for feeding a high-purity ammonia gas of the present invention comprises the sealing part and/or the gas contacting part which comprise a halogen-free resin. The gas flow path of feeding a high-purity ammonia gas is constituted by the above-described high-purity ammonia gas-feeding apparatus, and thereby a high-purity ammonia gas can be fed to an apparatus for producing a semiconductor device without deteriorating the gas purity.

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